

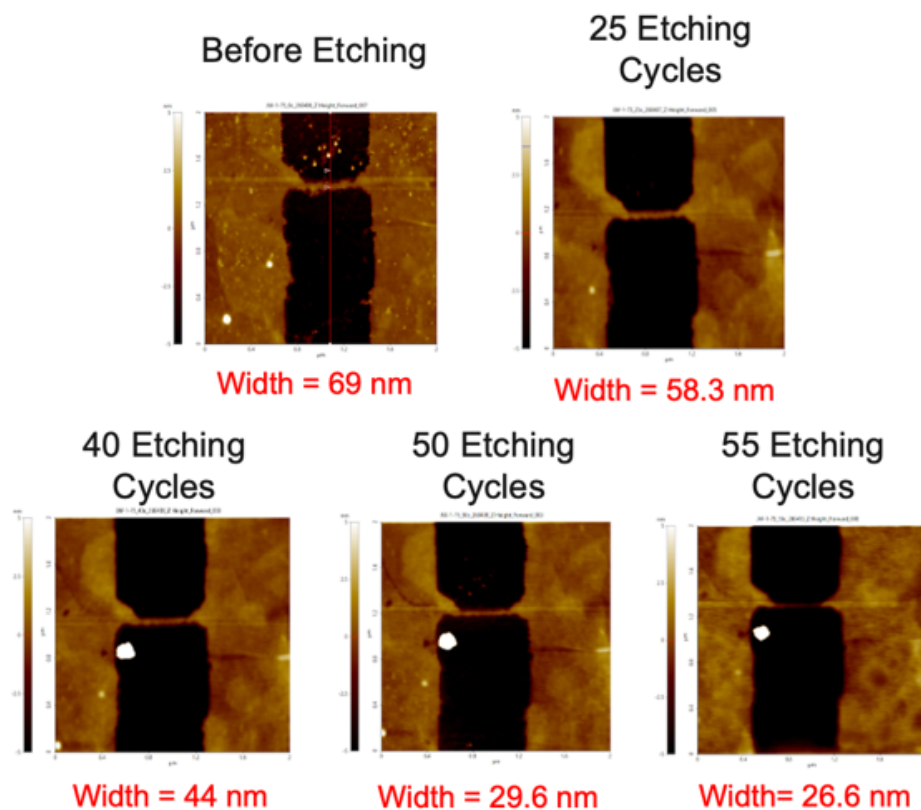


Figure 1. AFM images of MoS₂ nanoribbons versus number of thermal ALE cycles. MoS₂ thermal ALE was performed at 150 °C using sequential O₃ and SOCl₂ exposures. Width and line edge roughness of the MoS₂ nanoribbons are both reduced versus number of etching cycles.

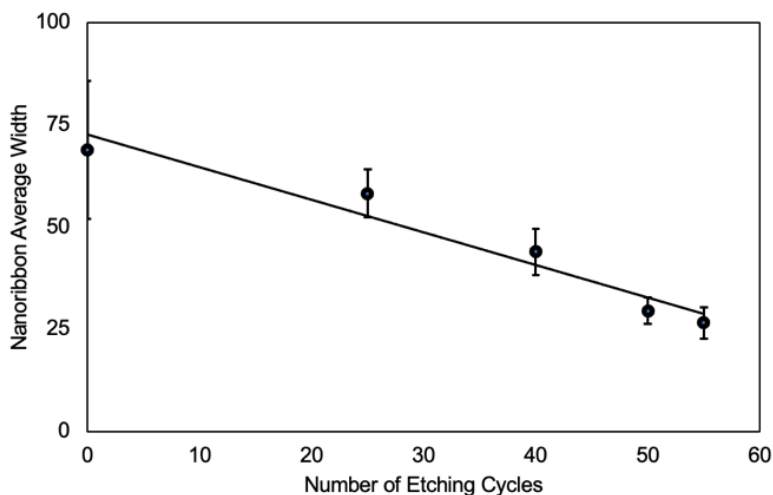


Figure 2. Average width of the MoS₂ nanoribbons versus number of etching cycles. The lateral etch rate was 3.9 Å/cycle.